

Abnormal oxidation of nickel silicide on N-type substrate and effect of preamorphization implantation

Yun JG, Soon-Young OH, Hee-Hwan JI, Huang BF, Park YH, Wang JS, Park SH, Bae TS, Lee HD.

Japanese Journal of Applied Physics, Part 1: Regular Papers and Short Notes and Review Papers

2004; 43(10):6998-6999

ARTICLE IDENTIFIERS

DOI: 10.1143/JJAP.43.6998

PMID: unavailable

PMCID: not available

JOURNAL IDENTIFIERS

LCCN: not available

pISSN: 0021-4922

eISSN: not available

OCLC ID: not available

CONS ID: not available

US National Library of Medicine ID: not available

This article was identified from a query of the SafetyLit database.